



JPL



NORTHROP GRUMMAN



Engineered Carbon Nanotube Materials for High-Q Nanomechanical REsonators

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Jet Propulsion Laboratory

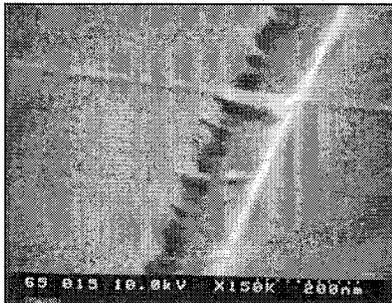
Jimmy Xu

Brown University

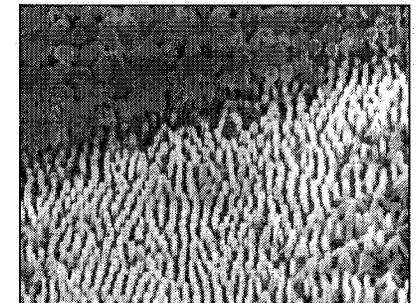
Douglas Adam, Rob Young

Northrop Grumman

suspended nanotube



NT array with electrode



NT03

Seoul, Korea, 7/11/03

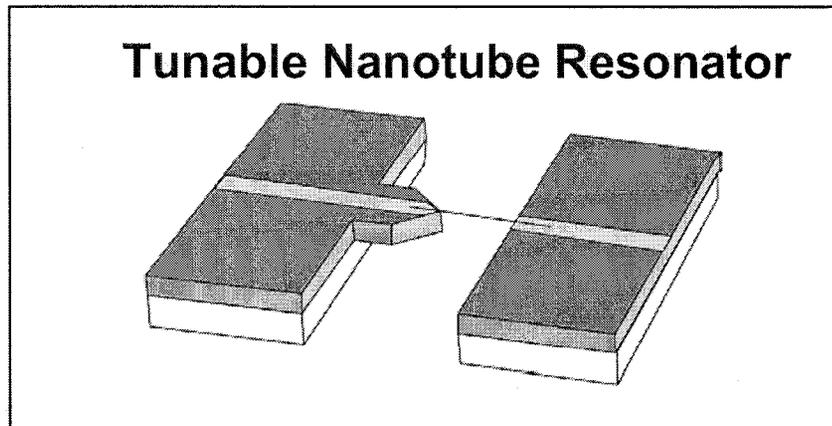


Goals / Approach

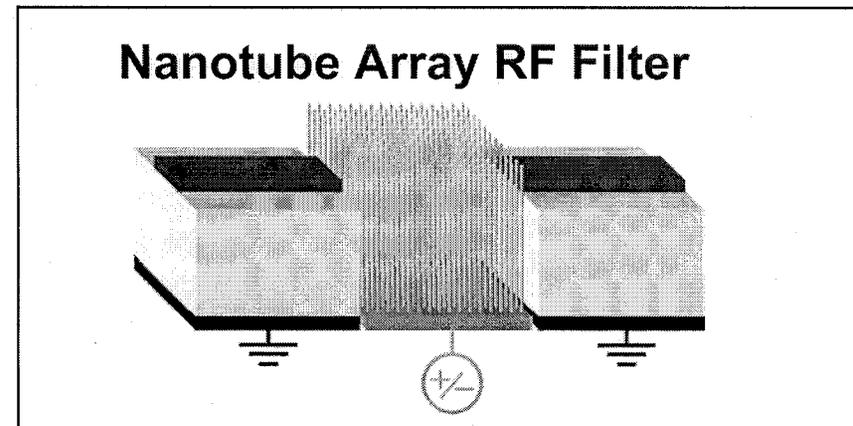


- **Demonstrate high-Q mechanical oscillators aimed at signal processing and based on carbon nanotubes: 1) a tunable nanotube resonator and 2) a nanotube array RF filter**

A single horizontal nanotube device for narrow-band detection:



A vertical nanotube array device for high-Q RF power signal processing:



- **Parallel efforts to develop both in-plane single nanotube resonators as well as vertical array power devices**
- **Basic fabrication approach:**
 - Use carbon nanotubes due to excellent mechanical, thermal, and electrical properties
 - *Grow nanotubes in situ with integrated electrodes*

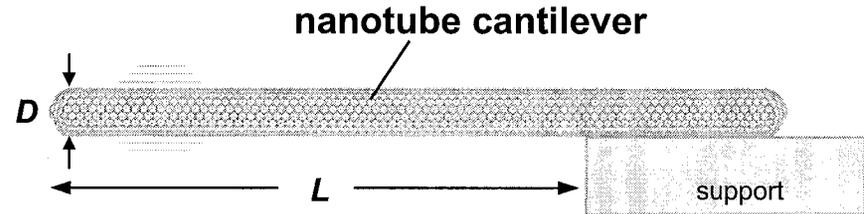


Nanotube mechanical resonators

- Fund. cantilever resonant frequency, f_0 , given by:

$$f_0 = \frac{(1.875)^2}{8\pi} \frac{1}{L^2} \sqrt{D^2 + D_i^2} \sqrt{\frac{E_b}{\rho}}$$

Poncharal et al., Science (1999)



Length:	500 nm	200 nm	100 nm	50 nm
f_0 :	213 MHz	1.3 GHz	5.3 GHz	21.3 GHz

- Resonant frequencies can range from MHz to GHz

10 nm OD SWNT, $E_b = 1$ TPa, $\beta_1=1.875$, $\rho = 1.33$ g/cm³

- Nanotubes enable high f_0 and small force constants

- Small k gives high sensitivity to input signals, low power operation, improved tunability (M. Roukes, Sensor and Act. Workshop, Hilton Head, 2000)
- Natural nanoscale dimensions allow large aspect ratios and GHz f_0 without heroic lithography effort: $f_0 \propto (D/L^2)$ and $k \propto (D/L)^3$
- But, also get increased sensitivity to environmental effects...

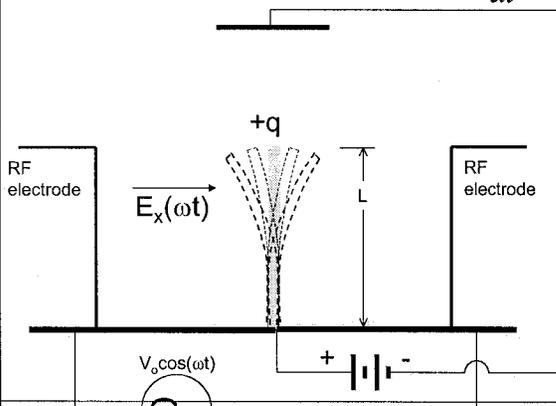
NT resonator modeling - Highlights

- Modeling is progressing – developing Equations of Motion and approximate circuit models for coupling to nanotube resonators:

Selected example – Northrop Grumman analysis:

1-D Eq. Of Motion charged Wheat stalk nanotube.

Newton's Law: $F_{tot} = Ma = M \frac{d^2x}{dt^2} = -kx - M\beta x^3 - 2M\lambda \frac{dx}{dt} + qE_{x0} \cos(\omega t)$



Linear spring cantilever:

$$k = \frac{3EI}{L^3} \quad I = \frac{\pi}{4}(R^4 - R_i^4)$$

Zero non-linear spring $\beta = 0$

Viscous damping: $\frac{2\lambda}{\omega_R} = \frac{1}{Q}$

$$Q = \frac{\mu}{\pi \rho R^2 \Gamma_i(\omega_R) + \Gamma_r(\omega_R)} \quad \Gamma(\omega) = 1 + \frac{4iK_1(-i\sqrt{iRe})}{\sqrt{iRe} K_0(-i\sqrt{iRe})} \quad Re = \frac{\rho \omega R^2}{\mu}$$

- The JPL RF group (Larry Epp and Dan Hoppe) is working with NGC:

- To determine approximate solutions to wave equation
- To develop circuit models and techniques for efficient matching to the NT resonators
- To design RF waveguide structures for coupling to NT devices (see next page)

Leads to Wave Equation for a nanotube "wheat field":

$$\omega = \sqrt{\frac{k}{M}} + \frac{q^2}{\pi \epsilon_0 d^3 M} [1 - \text{Cos}(sd)] \quad \text{for } sd \ll 1 \quad \omega = \sqrt{\frac{k}{M}} + \frac{q^2 s^2}{2\pi \epsilon_0 d M}$$

mechanical resonance of single nanotube

stiffening and coupling due to electrostatic forces

mass

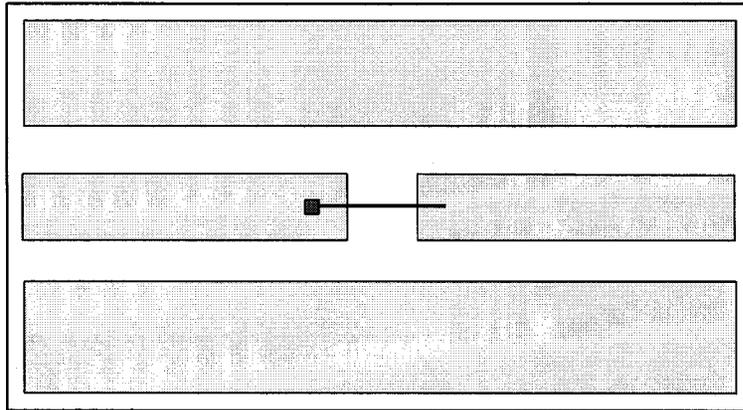
separation between nanotubes

spring constant

charge

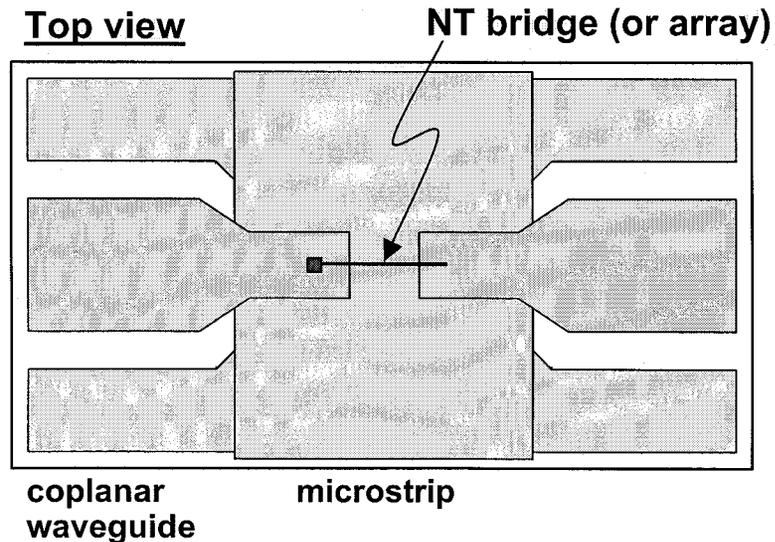
wave number

a) Coplanar waveguide *(lateral or vertical NT)*

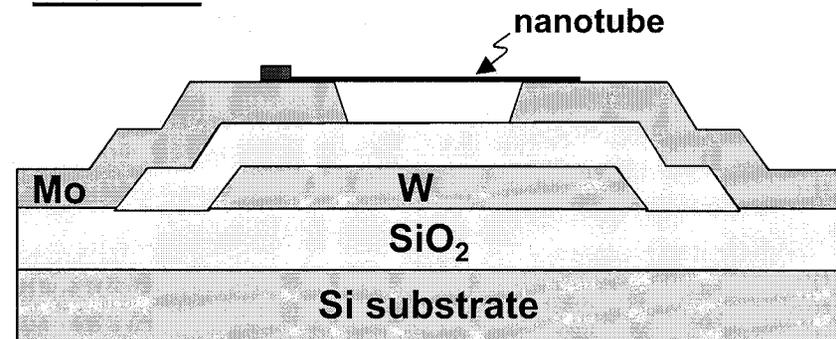


- CPW-to- μ strip provides efficient coupling to both suspended NT bridges and vertical NT arrays
- Relatively simple fabrication for lateral NT devices
- Vertical array process under development

b) Coplanar waveguide to microstrip transition

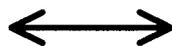


Side view



We need:

“Perfectly” crystalline nanotubes



High v and small Δv ,
reduced environ. effects

Uniform diameters, lengths



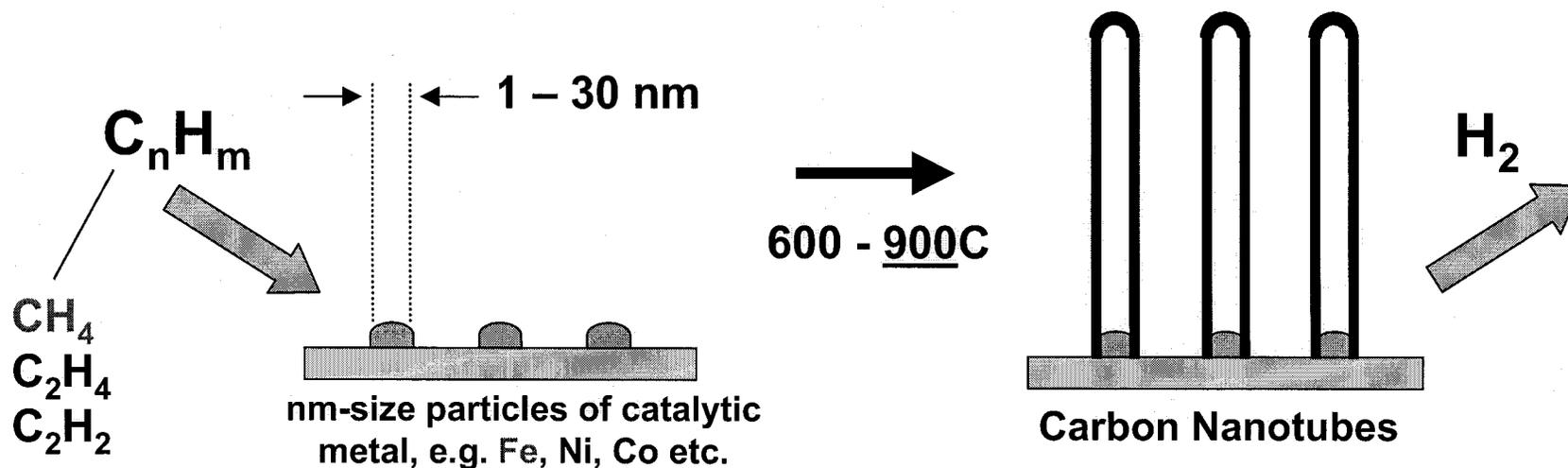
Narrow Δv

Directed Growth



Device integration

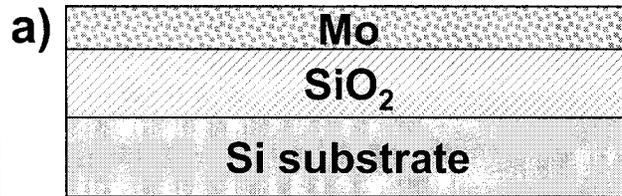
Chemical Vapor Deposition (CVD) of carbon nanotubes:



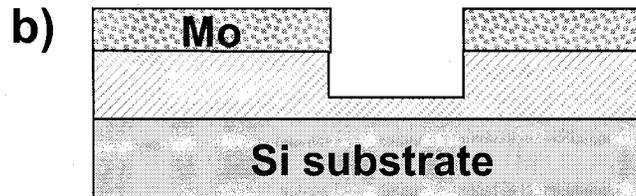
Important: size and position of catalytic particles determine size and position of resulting CNT

Process for growth of suspended CNT bridges with integrated molybdenum electrodes

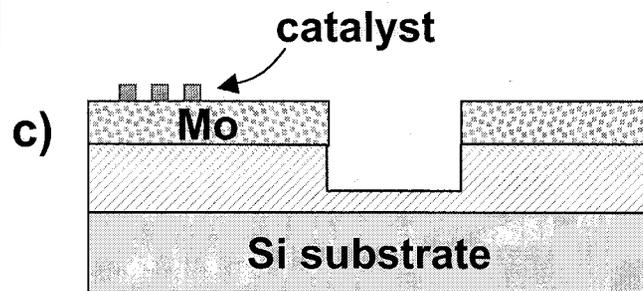
- Minimizes nanotube processing after growth
- Mo electrodes provide high quality electrical contacts



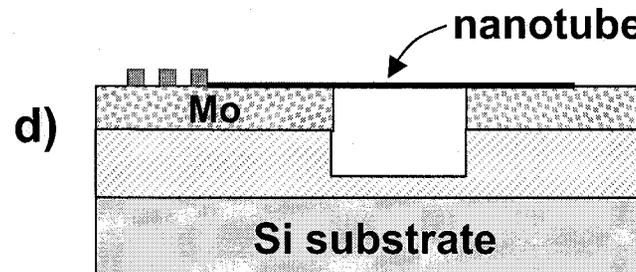
Deposit Mo on Si/SiO₂



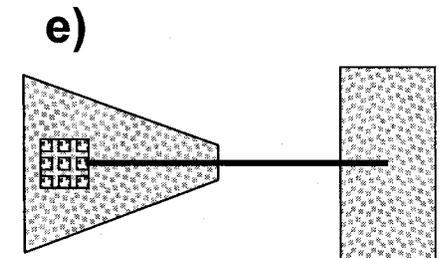
Etch Mo-SiO₂ bilayer to define elec. & trench



Liftoff catalyst



Grow nanotube



Top view

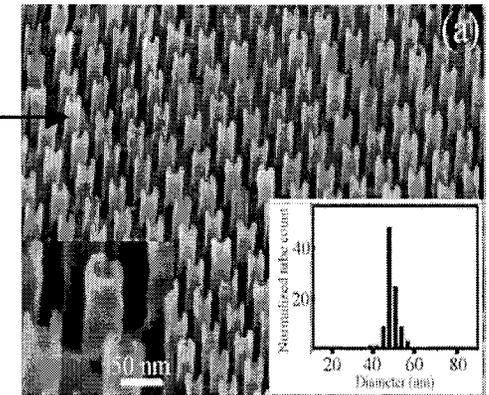
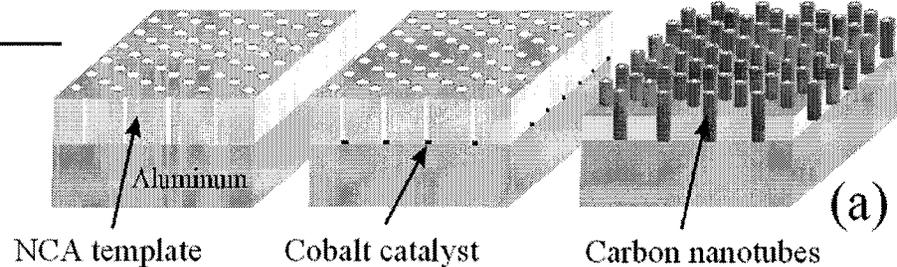
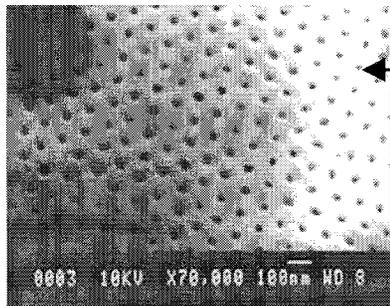
Related to H. Dai process, APL 81, 913 (7/29/02)



Alumina Nanopore Process for Uniform Vertical Nanotube Arrays

Prof. Jimmy Xu, Brown University:

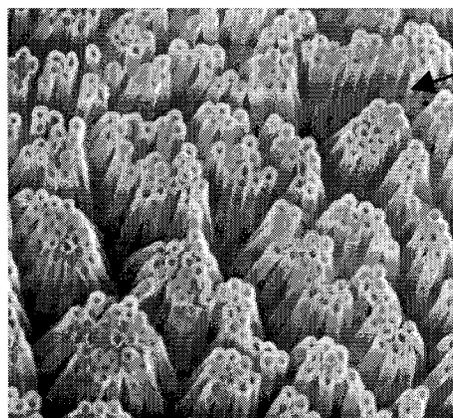
Al anodization → Co deposition → C₂H₂ pyrolysis



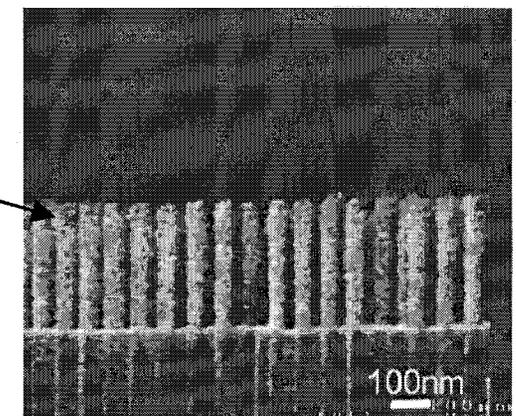
Free-standing Al foil process

- Anodized Al forms ordered pores - template for CNT array
- *Nanotubes are uniform in diameter, length, and spacing*

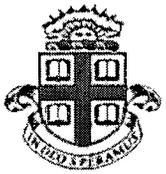
Baseline process under control



- Wet etch for removing alumina can lead to tube sticking (chromic+phosphoric)
- Improved process with dispersants in etch greatly reduces sticking
- Free-standing tubes up to 800nm long with 20:1 aspect ratios are now possible (~ 2.7GHz f₀)



(with 25nm Au/Pt coating)

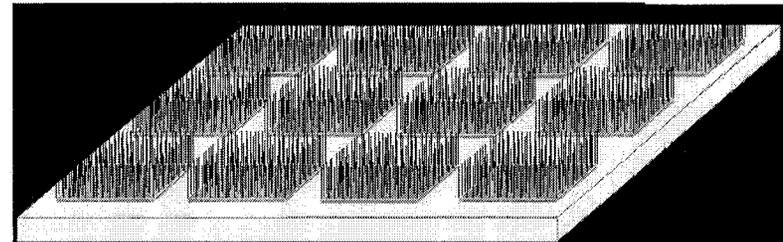


Carbon nanotube array device processing

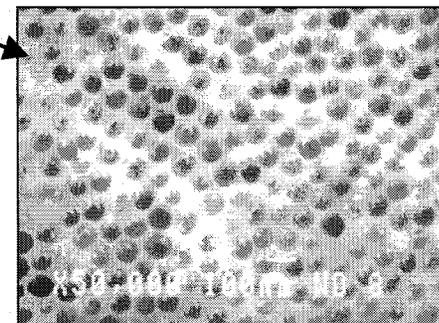


Aluminum nanopore process on Si:

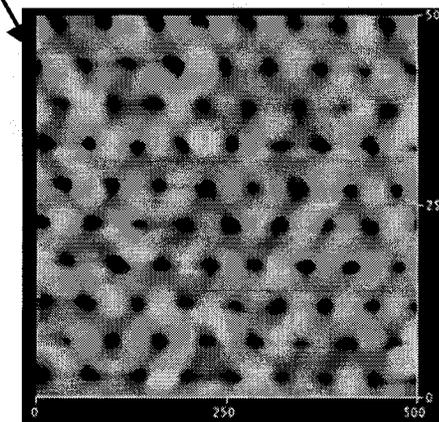
- Requires deposition of high purity, very smooth Al films on Si
- Al film typically much thinner than Al foil in standard process (~3 μm vs >15 μm)
 - Self-ordering of pores more difficult
 - Investigating ebeam-patterned pore nucleation sites
- Buried electrodes may be needed:
 - Must be compatible with high temp. NT growth and with AlO_x etching
 - Investigating tungsten electrodes
- Patterning of arrays and array electrodes
 - Array patterning - pre-pattern Al, window anodization
 - Electrode patterning after NT growth



Want patterned arrays on Si with electrodes and controlled array properties



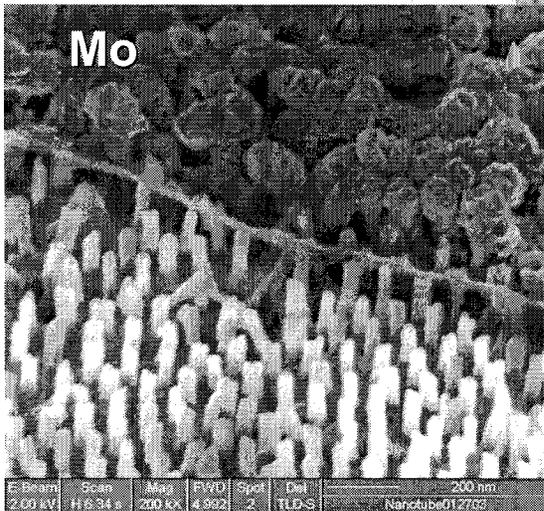
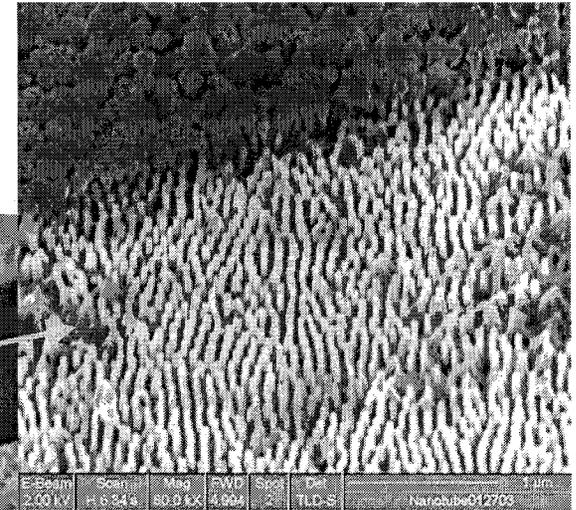
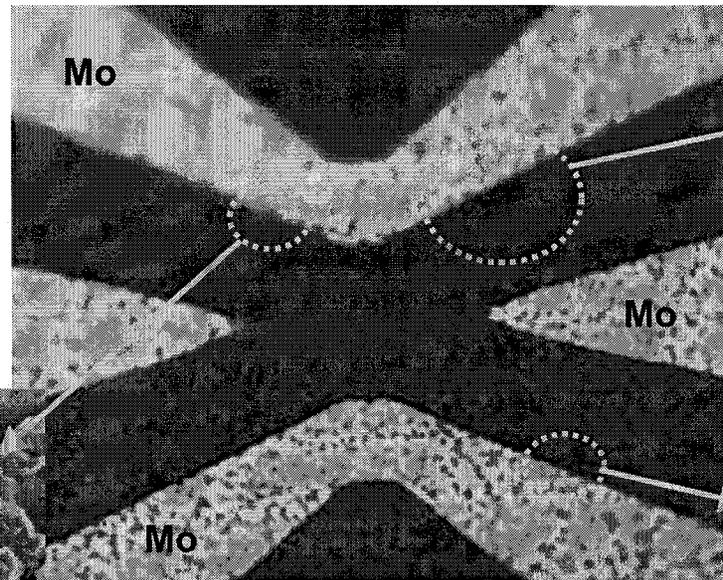
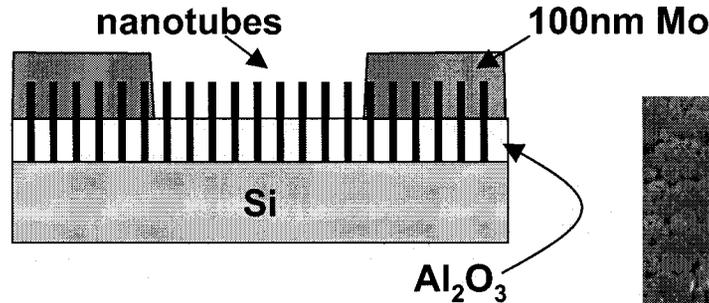
Pore array with NTs produced in anodized Al on silicon wafer



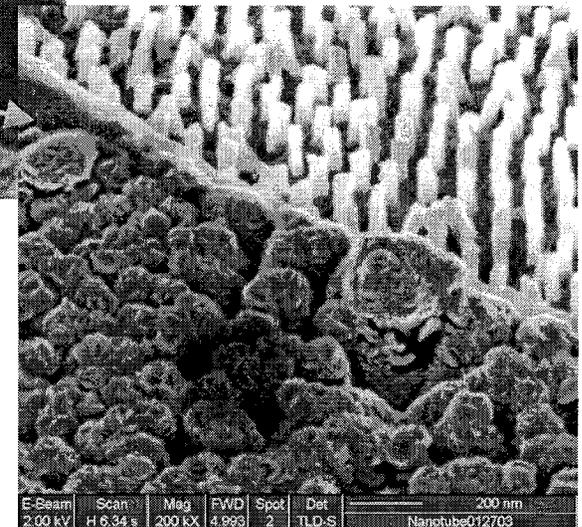
E-beam patterned hole array in PMMA on Al for etching of anodization nucleation sites - 20nm dots on 60nm centers

Patterned Mo electrodes

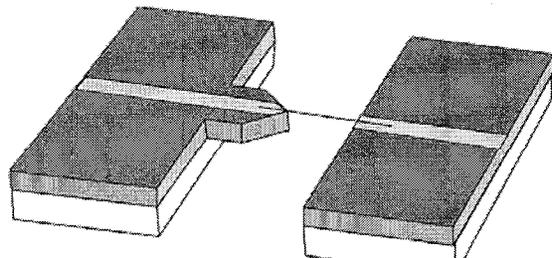
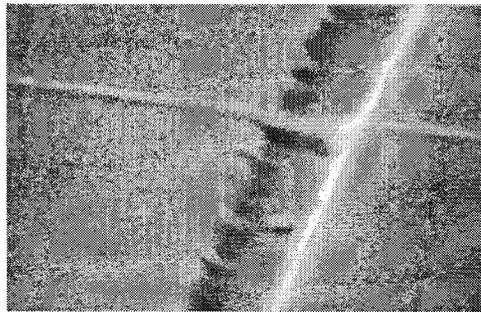
- Liftoff processing on Brown U. NT arrays
- RF-compatible CPW electrodes
- Nanotubes survive processing without de-adhering or tube-to-tube sticking



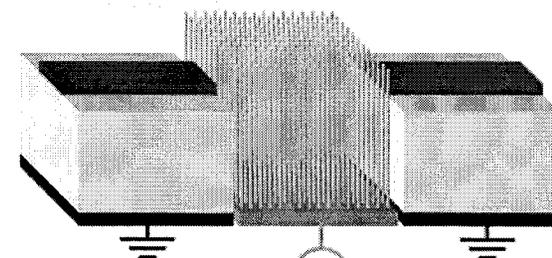
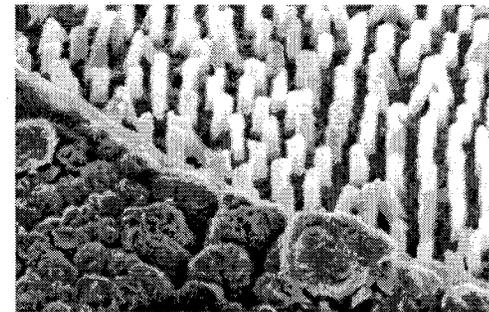
- Electrical measurements show acceptable electrode conductivity and isolation



- **Developing high-Q mechanical oscillators based on carbon nanotubes**
 - **Tunable nanotube resonator based on suspended nanotube bridge**
 - **Narrow band RF filter using CNT array in microstrip waveguide**
- **Modeling and process development in progress for design and fabrication of in-plane and vertical nanotube devices**
- **Prototype device structures have been fabricated**



Tunable Nanotube Resonator



Nanotube Array RF Filter

